

	Hits	Search Text	DBs
42	21	((reticle or mask or photomask) near16 EUV near22 (illuminat\$4 or irradiat\$4 or expos\$4 or project\$4) near16 (photoresist or resist) near12 reflect\$4 near20 system)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
43	5	((reticle or mask or photomask) near16 EUV near22 (illuminat\$4 or irradiat\$4 or expos\$4 or project\$4) near16 (photoresist or resist) near12 reflect\$4) and ((chromium or chrome) same (mask or reticle or photomask) same (absorp\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
46	77	((reticle or mask or photomask) near16 EUV near22 (illuminat\$4 or irradiat\$4 or expos\$4 or project\$4) near16 (photoresist or resist)) and (EUV near9 (mask or reticle) near12 reflect\$4 near20 (absorptive or absorb\$4 or system))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB